

Resource Summary Report

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Kloe: UV-KUB 2 - UV-LED masking system

RRID:SCR_021141

Type: Tool

Proper Citation

Kloe: UV-KUB 2 - UV-LED masking system (RRID:SCR_021141)

Resource Information

URL: <https://www.kloe-france.com/en/laser-lithography/photolithography-systems/uv-exposure/uv-kub-2>

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Description: Compact exposure masking system is UV-LED masking system equipped with LED based optical head, collimated and homogeneous. One level mask aligner. Its masking function enables to reach resolutions less than 1um. This system is compatible with any of photoresists such as AZ series, Shipley series, SU-8 and K-CL series.

Synonyms: UV?KUB 2 masking system, UV-KUB 2

Resource Type: instrument resource

Keywords: KLOE SA, UV LED masker, exposure masking system, instrument, equipment, USEDit

Resource Name: Kloe: UV-KUB 2 - UV-LED masking system

Resource ID: SCR_021141

Alternate IDs: Model_Number_UV-KUB 2

Record Creation Time: 20220129T080354+0000

Record Last Update: 20260829T182712+0000

Ratings and Alerts

No rating or validation information has been found for Kloe: UV-KUB 2 - UV-LED masking system.

No alerts have been found for Kloe: UV-KUB 2 - UV-LED masking system.

Data and Source Information

Source: [SciCrunch Registry](#)

Usage and Citation Metrics

We have not found any literature mentions for this resource.